

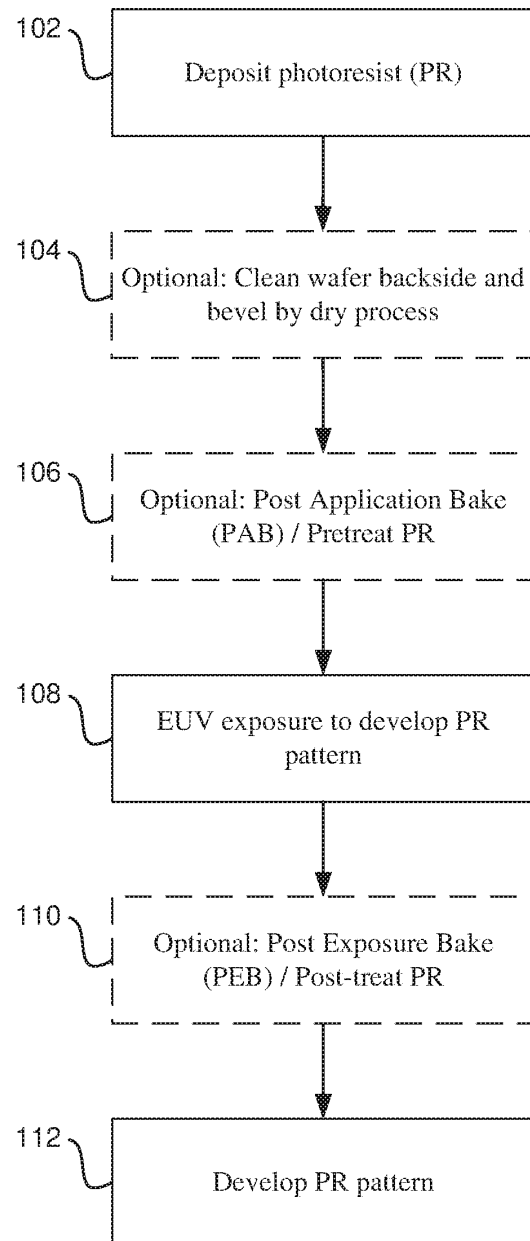
**FIG. 1**

FIG. 2A

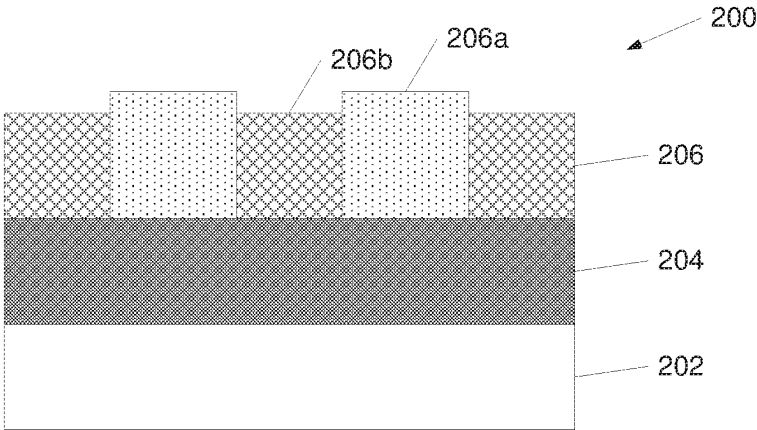


FIG. 2B

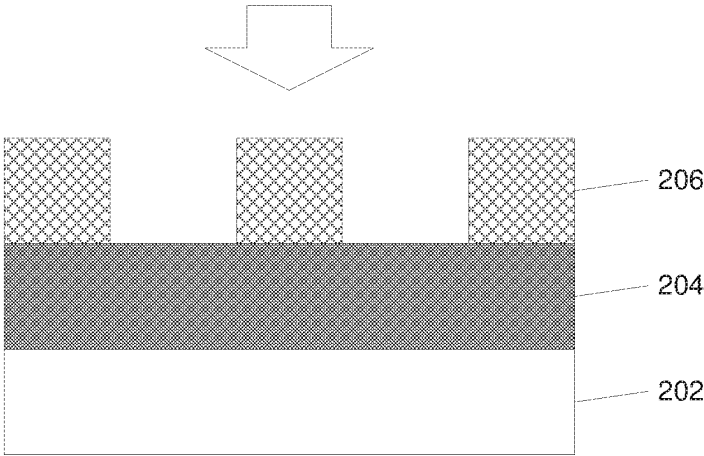
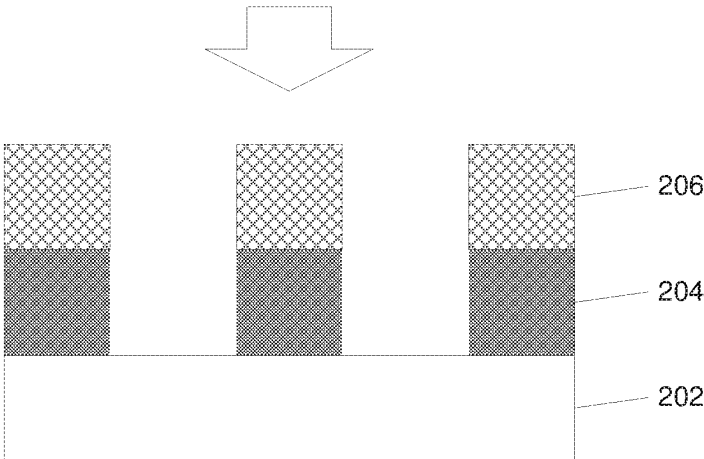
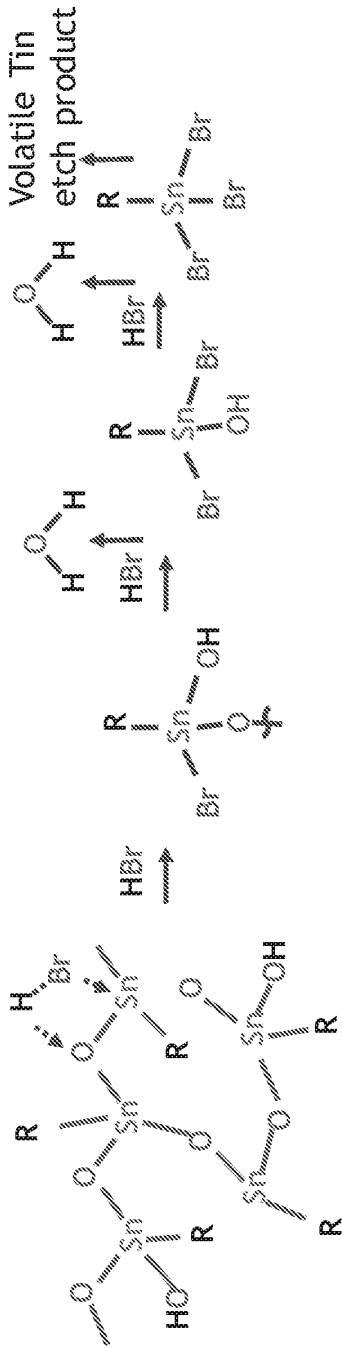


FIG. 2C



Unexposed Photoresist:



Exposed Photoresist:

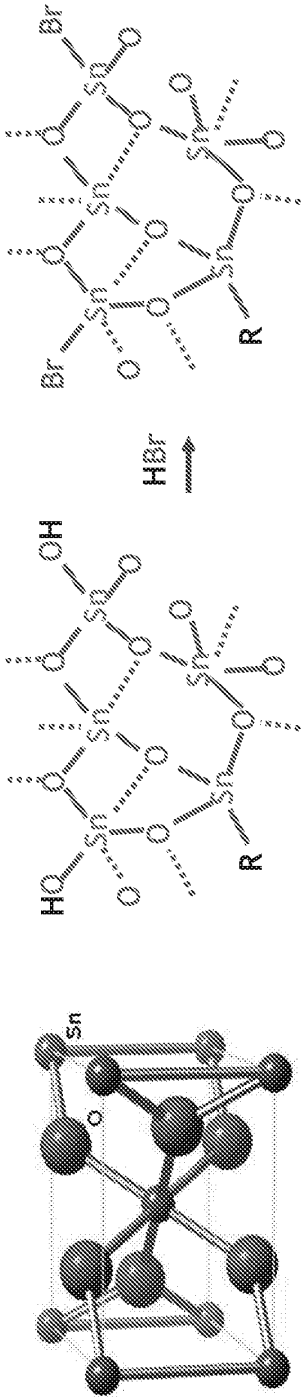


FIG. 3

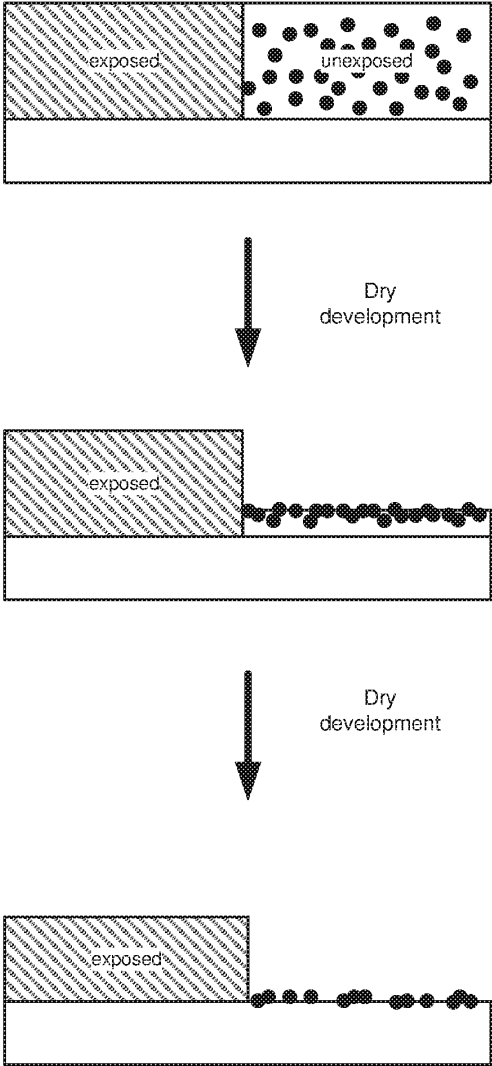


FIG. 4A

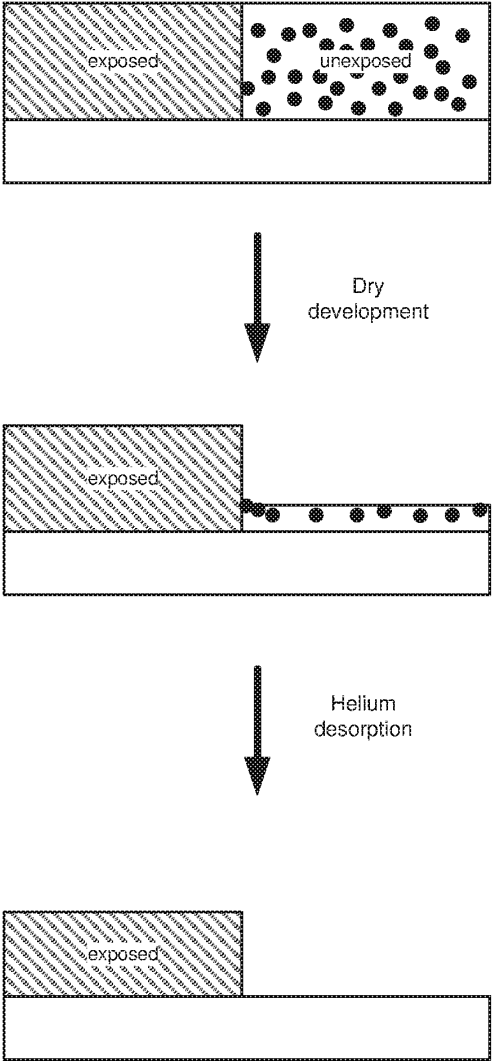
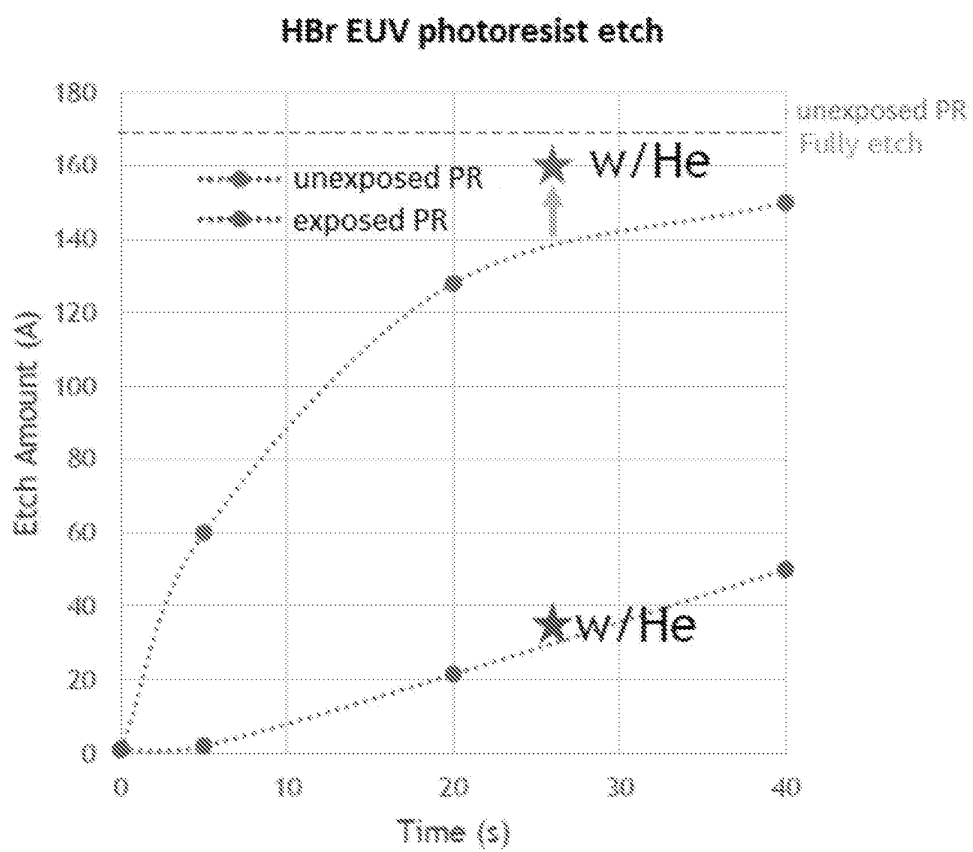


FIG. 4B

**FIG. 5**

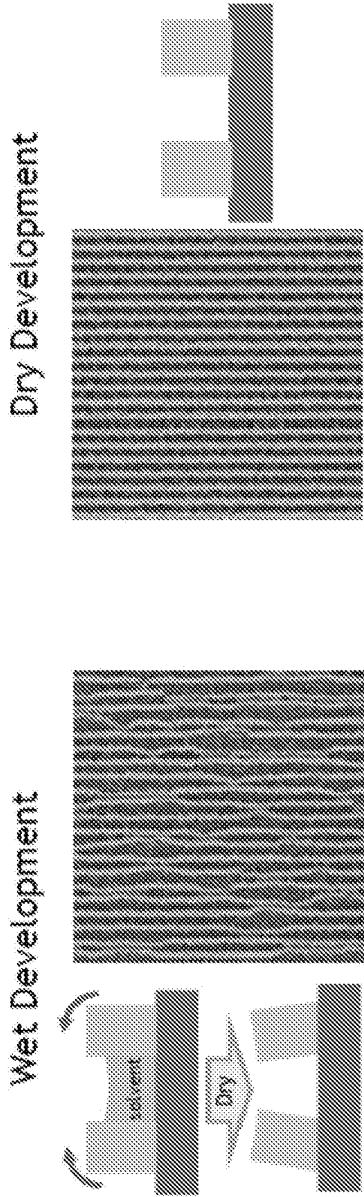


FIG. 6A

FIG. 6B

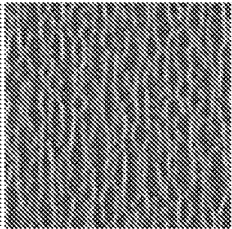
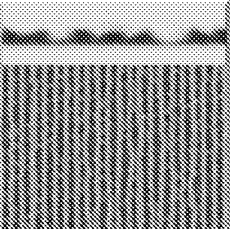
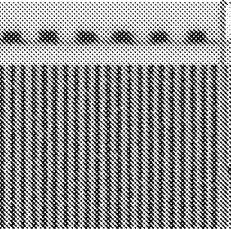
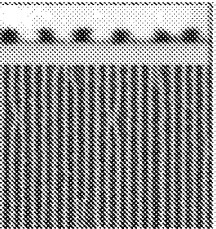
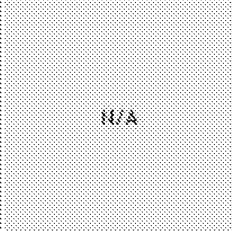
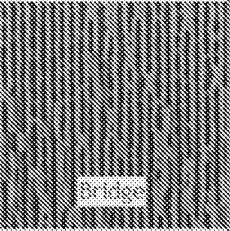
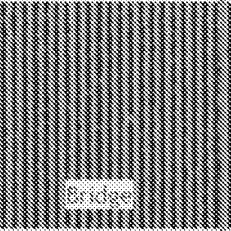
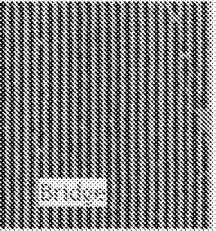
Location	-9, 0	-4, 6	-4, -2	-4, -6
Dose	38		43	
Focus	-0.05	-0.11	-0.03	0.01
Wet Development				
LnCD/LWR			13.0/4.1	
Pattern Transfer				
LnCD/LWR			14.6/4.7	

FIG. 7A

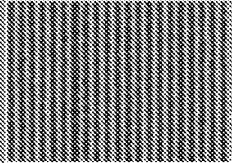
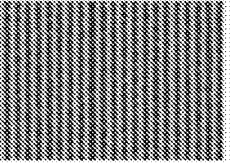
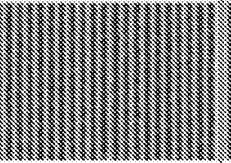
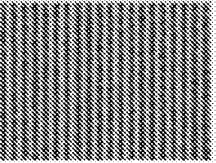
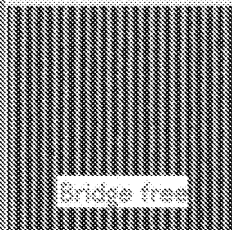
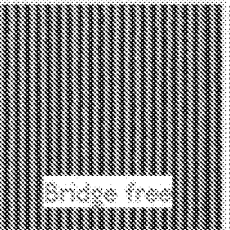
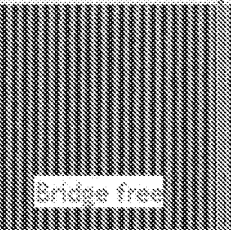
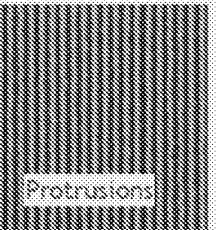
Location	-9, 0	-4, 6	-4, -2	-4, -6
Dose	38		43	
Focus	-0.05	-0.11	-0.03	0.01
Dry Development				
LnCD/LWR	10.4/3.8	11.7/3.9	12.1/3.8	11.8/4.5
Pattern Transfer				
LnCD/LWR	10.2/3.7	11.9/3.6	12.2/3.3	12.3/3.9

FIG. 7B

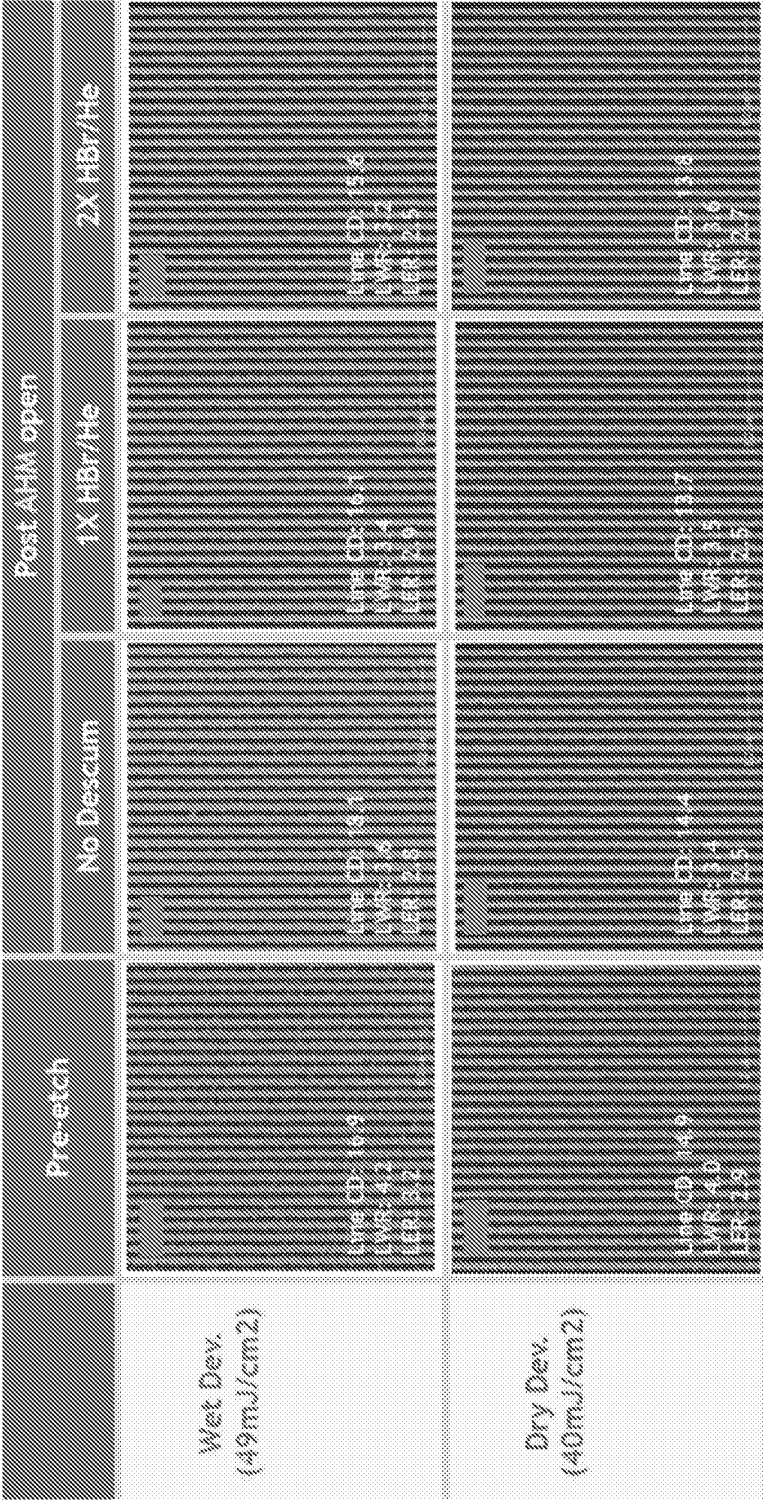


FIG. 8

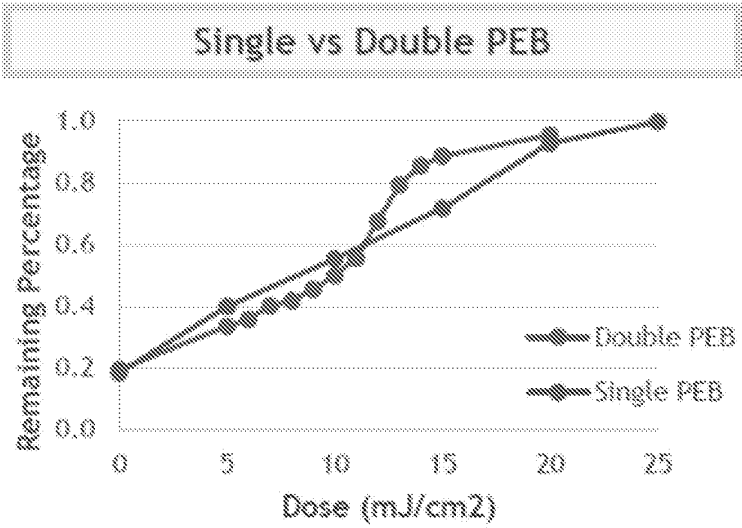


FIG. 9A

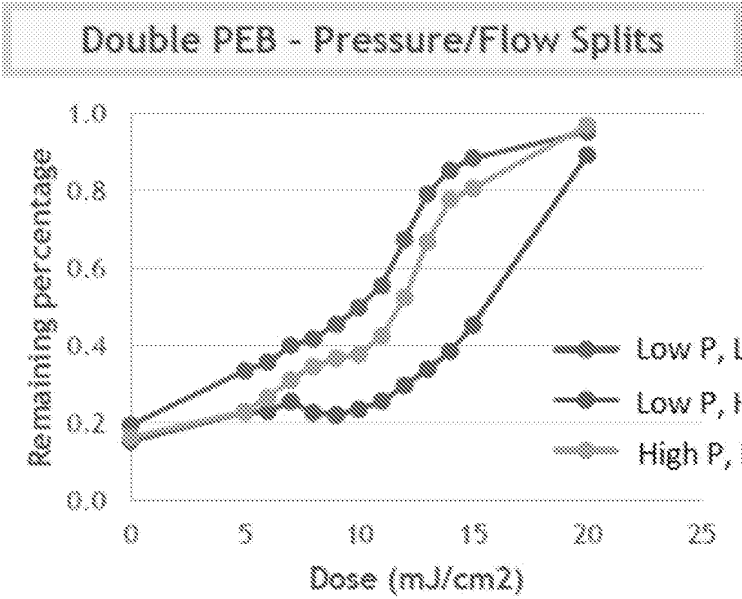
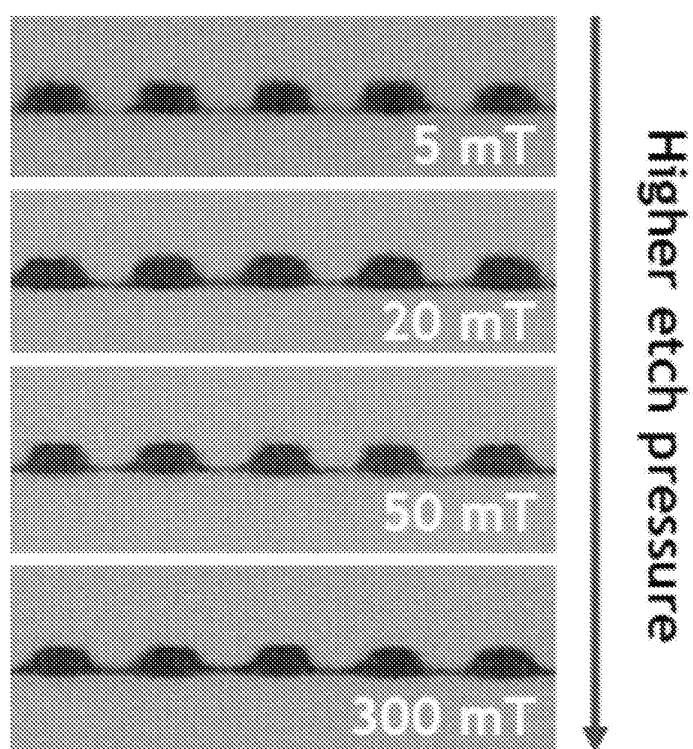


FIG. 9B

**FIG. 10**

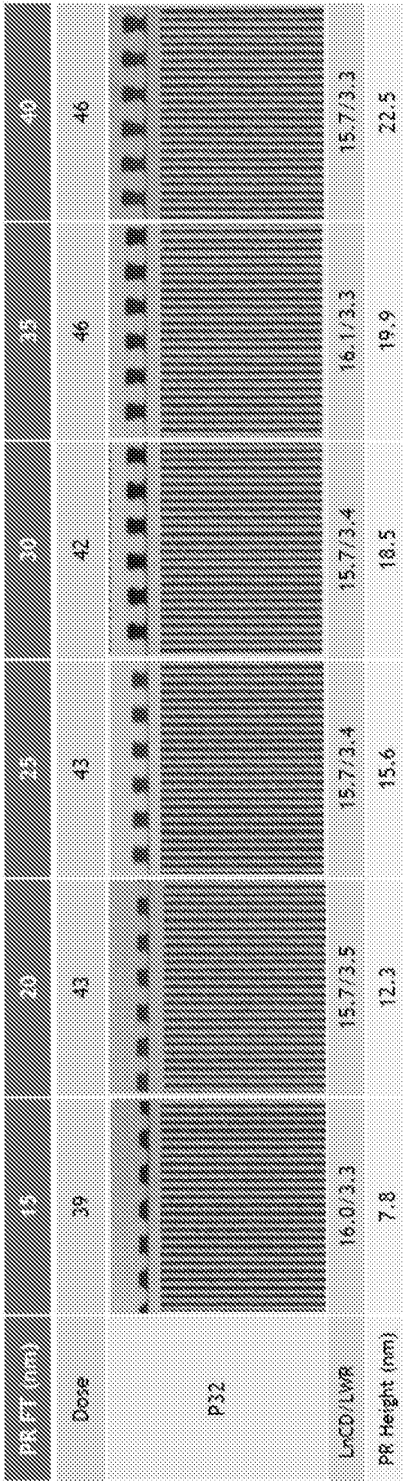


FIG. 11A

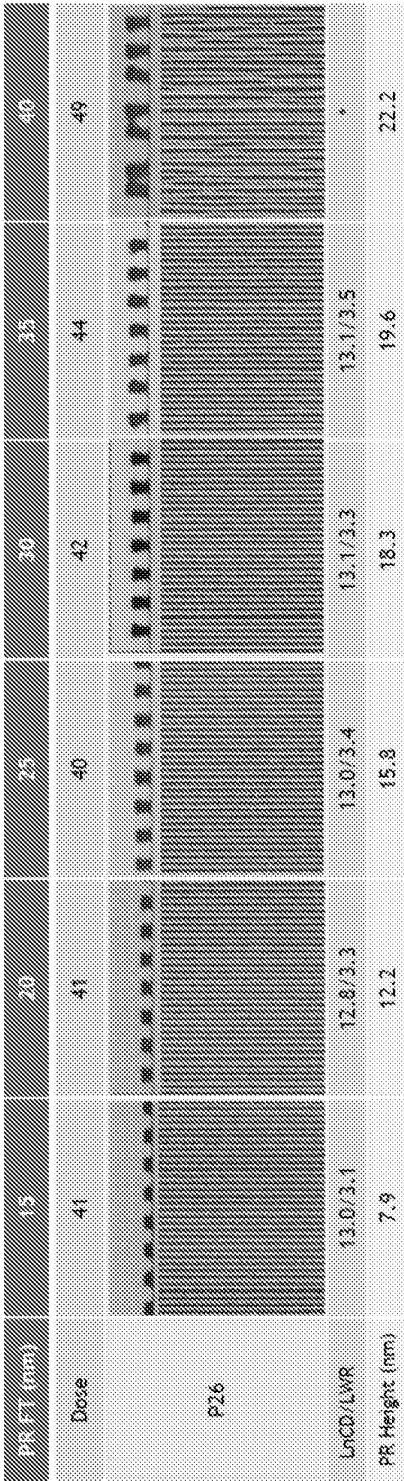


FIG. 11B

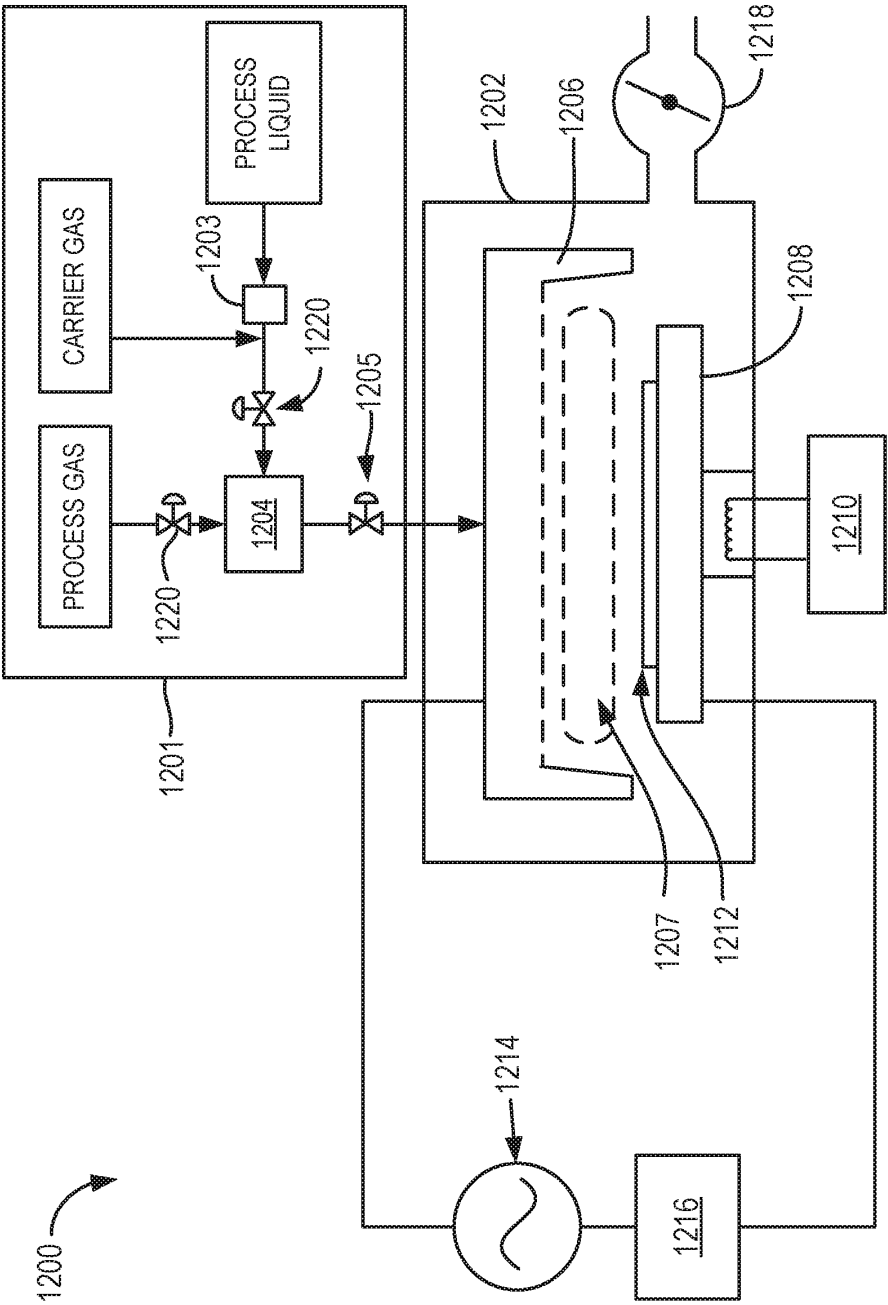
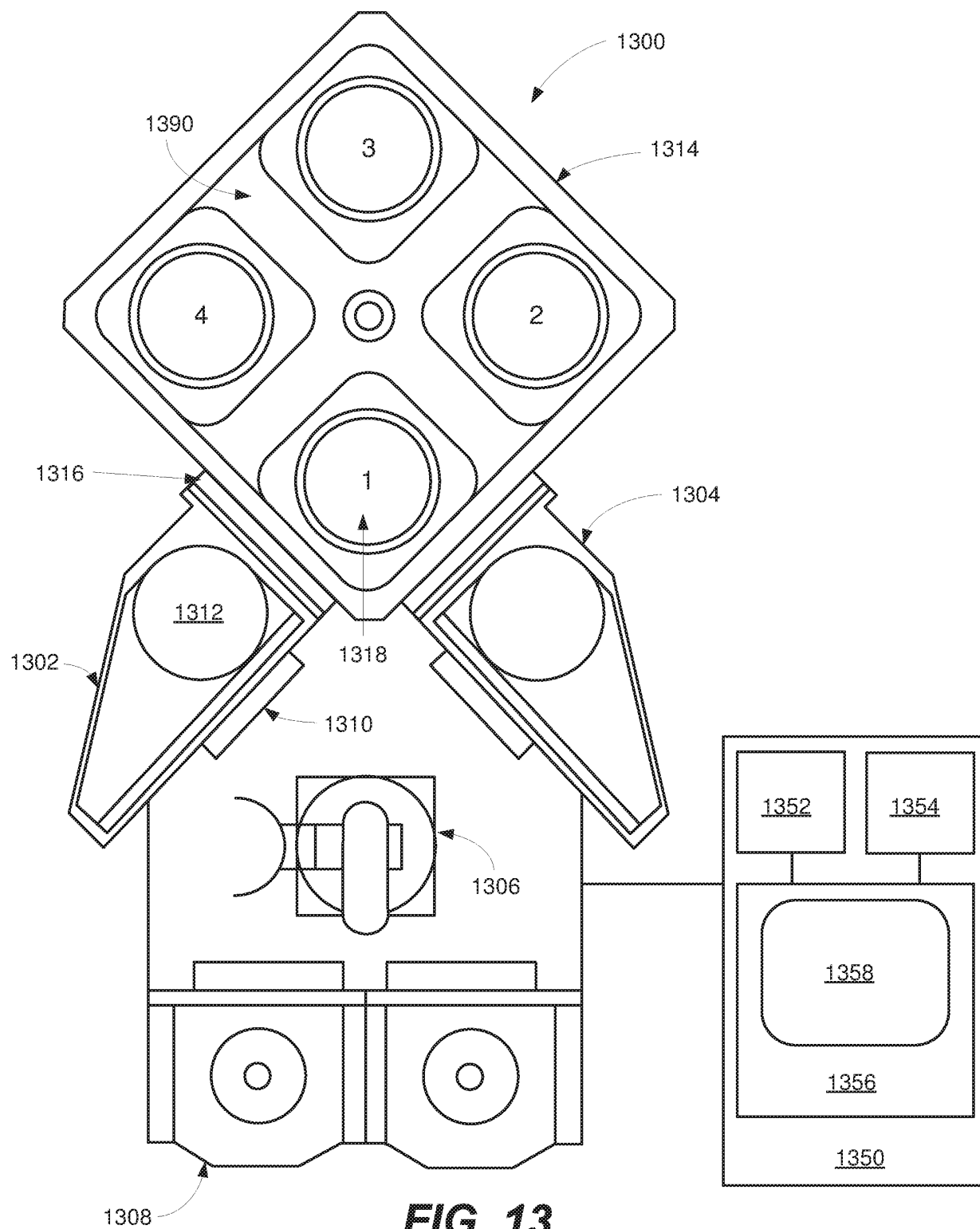
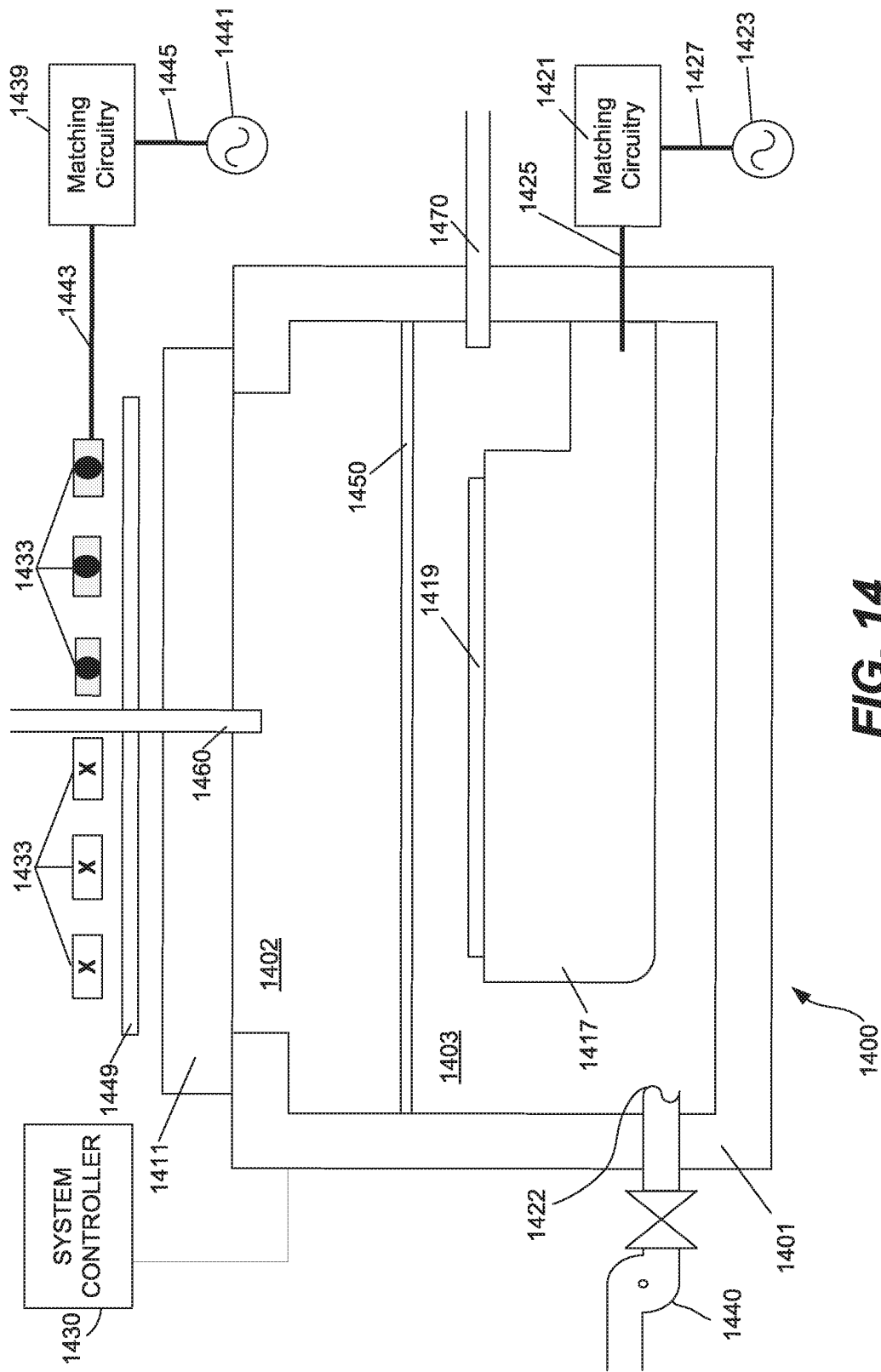
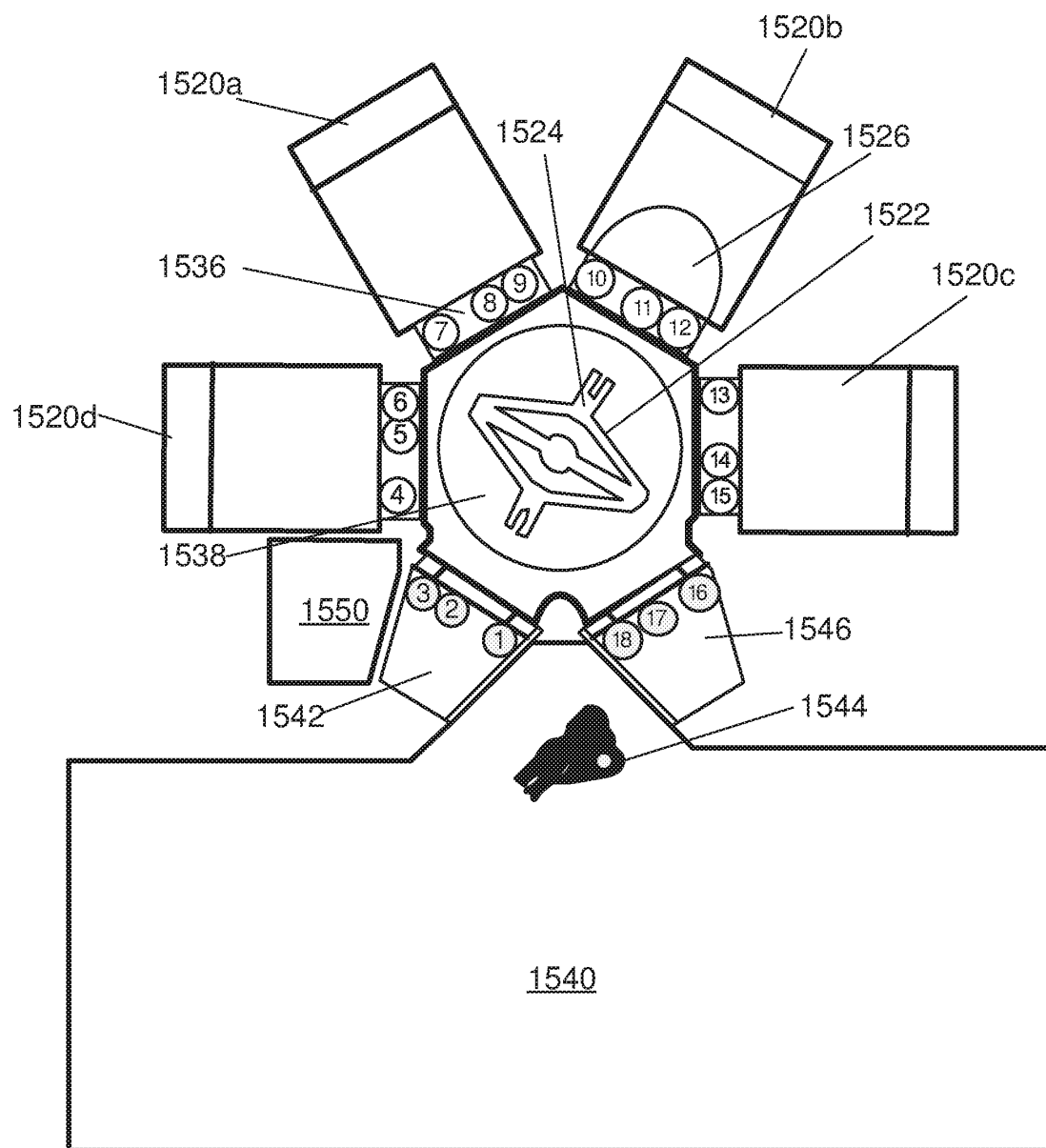


FIG. 12





**FIG. 15**